

Photomask Japan 2018  
Best Paper Award Winners



Best Oral Presentation:

Program No.	Presentation Title	Name	Affiliation
6-2 [BACUS]	Minimizing "Tone Reversal" during 19x nm Mask Inspection	K. Seki (1), K. Badger (2), M. Yonetani (3), A. Birnstein (4), J. Heumann (4), T. Isogawa (1), T. Konishi (1), Y. Kodera (1)	(1)Toppan Printing Co., Ltd. (Japan), (2)GLOBALFOUNDRIES Inc. (USA), (3)Toppan Photomasks, Inc (USA), (4)Advanced Mask Technology Center (Germany)
12-3 [EMLC]	Development of closed-type EUV pellicle	Y. Ono, K. Kohmura, A. Okubo, D. Taneichi, H. Ishikawa, T. Biyajima	Mitsui Chemicals Inc. (Japan)
2-4	New Half-Tone Lithography Uses for FPD Proximity Printing	S. Kobayashi, K. Yoshida, M. Miyoshi, Y. Yoshikawa	HOYA Corporation (Japan)

Best Poster Presentation:

9A-3	Intra-field mask-to-mask overlay, separating the mask writing from the dynamic pellicle contribution	R. van Haren (1), S. Steinert (2), O. Mouraille (1), K. D'havé (3), L. van Dijk (1), R. Otten (1), D. Beyer (2)	(1)ASML (The Netherlands), (2)Carl Zeiss SMT GmbH (Germany), (3)IMEC (Belgium)
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Best Academic Poster Presentation:

9B-4 [BACUS]	Simulation of fogging electron trajectories in a scanning electron microscope	Y. Ito, T. Donga, K. Morimoto, M. Kotera	Major in Electrical, Electronic and Mechanical Engineering, Osaka Institute of Technology (Japan)
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